#2

Inventor:

John T. Moore

RECEIVED

OIPETHIE:

Methods of Forming Oxide Regions Over 8 Semiconductor

Substrates, and Methods of Forming Transistors Associated with

Semiconductor Substrates

Assignee:

Micron Technology, Inc.

Serial No.:

09/602,395

Filed:

June 22, 2000

## **INFORMATION DISCLOSURE STATEMENT**

## PURSUANT TO 37 C.F.R. §§ 1.56, 1.97 AND 1.98

In compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, the Examiner's attention is directed to the references listed on the attached Form PTO-1449 and copies of which are attached. No admission is made regarding whether all the submitted references are prior art.

Citation of these references is respectfully requested.

Respectfully submitted,

Data:

Attorney:

David G. Latwesen, Ph.D.

Reg. No. 38,533

Wells, St. John, Roberts, Gregory & Matkin, P.S.